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(71) Applicant (for all designated States except US): KORNIC SYSTEMS CORP. [KR/KR]; 605, Jung-ri, Dongtan-myeon, Hwaseong-si, Gyeonggi-do 445-813 (KR).

(72) Inventors; and

(75) Inventors/Applicants (for US only): SI, Sung Soo [KR/KR]; B-810, Hapjeong Yeollip, 397-2, Hapjeong-dong, Mapo-gu, Seoul 121-886 (KR). KIM, Seong Tae [KR/KR]; 513-2005, Jugong Apt., Yeongtong-dong,

Yeongtong-gu, Suwon-si, Gyeonggi-do 443-470 (KR). LEE, Seok Jeong [KR/KR]; 67-17, Guui 2-dong, Gwangjin-gu, Seoul 43-819 (KR). YEON, Kang Heum [KR/KR]; 102Ho, 1015-1, Yeongtong-dong, Yeongtong-gu, Suwon-si, Gyeonggi-do 443-470 (KR). SONG, Dae Seok [KR/KR]; 60-8, Bakdal-dong, Manan-gu, Anyang-si, Gyeonggi-do 430-030 (KR).

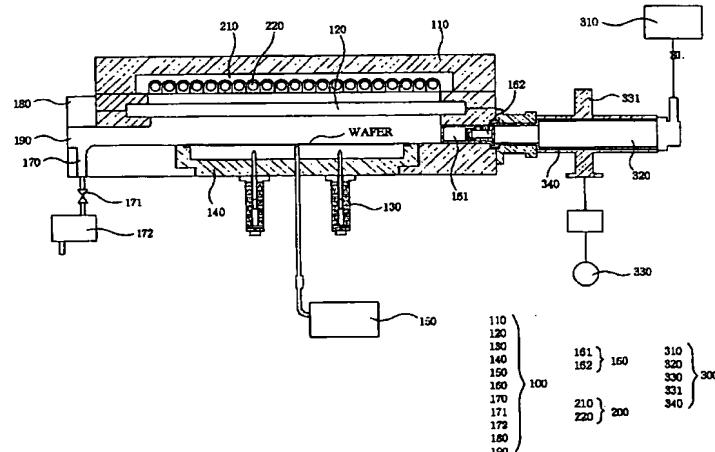
(74) Agent: HUH, Jin-Seok; 304 Yeongshin B/D, 832-3, Yeoksam-dong, Gangnam-gu, Seoul 135-080 (KR).

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